

the **abdus salam** international centre for theoretical physics

> (3) 人 The United Nations University

SMR.1073-4

ICTP-UNU-Microprocessor Laboratory Fifth Course on Basic VLSI Design Techniques

9 November - 4 December 1998

INTRODUCTION TO VLSI ASIC DESIGN AND TECHNOLOGY CMOS regular structures

Paulo Rodrigues S. MOREIRA CERN EP Division Building 14-6-014, F18300 CH-1211 Geneva 23 SWITZERLAND

These are preliminary lecture notes intended only for distribution to participants

k

2

Outline

- Introduction
- CMOS devices
- CMOS technology
- CMOS logic structures
- CMOS sequential circuits
- CMOS regular structures

CMOS regular structures

- Memory classification
- Write/read cycle
- Memory architecture
- Read-only memories
- Nonvolatile read-write memories
- Read-write memories
- Sense amplifiers

- Memory: logic element where data can be stored to be retrieved at a later time
- Read-Only Memory (ROM)
 - The information is encoded in the circuit topology
 - The data cannot be modified: it can only be read
 - ROM's are not volatile. That is, removing the power source does not erase the information contents of the memory.

- Read Write Memories (RWM)
 - RWM's allow both reading and writing operations
 - RWM can be of two general types:
 - Static: the data is stored in flip-flops
 - Dynamic: the data is stored as charge in a capacitor
 - Both types of memories are volatile, that is, data is lost once the power is turned off
 - Dynamic memories require periodic "refresh" of its contents in order to compensate for the charge loss caused by leakage currents in the memory element

- Nonvolatile Read-Write Memories (NVRWM)
 - These are non volatile memories that allow write operations
 - However:
 - The write operation takes substantially more time than the read operation
 - For some types of NVRWM's, the write operation requires special lab equipment
 - Examples of such memories are:
 - EPROM (Erasable Programmable Read-Only memory)
 - E²PROM (Electrically Erasable Programmable Read-Only Memory)

- Memories can also be classified according to the way they allow access to the stored data:
 - Random Access: memory locations can be read or written in a random order
 - First-In First-Out (FIFO): The first word to be written is the first word to be read
 - Last-In First-Out (LIFO): The last word to be written is the first word to be read (stack)
 - Shift Register: information is streamed in and out.
 It can work either as a FIFO or as a LIFO

Write/read cycle

- <u>Read-access time:</u> delay between read request and data valid
- <u>Write-access time:</u> delay between write request and the actual writing
- <u>Read or write cycle time</u>: minimum time required between successive read or write operations



- The memory is organized in N words, each of M bits wide
- One word at a time is selected for read/write using a select signal
- A decoder is used to convert a binary encoded address into a single active word select line
- This structure is not practical, it results in very big aspect ratios



- Memories are organized to be almost square in layout:
 - Multiple words are stored in the same row and selected simultaneously
 - The correct word is then selected by the column decoder
 - The word address is split in two fields:
 - row address: enables one row for R/W
 - column address: selects a word within a row
 - Even this structure is impractical for memories bigger than 256Kbits



- The silicon area of large memory cells is dominated by the size of the memory core, it is thus crucial to <u>keep the size of the basic</u> <u>storage cell as small as possible</u>
- The storage cell area is reduced by:
 - reducing the driving capability of the cell (small devices)
 - reducing the logic swing and the noise margins
- Consequently, sense amplifiers are used to restore full rail-to-rail amplitude



- Large memories start to suffer from speed degradation due to wire resistance and capacitive loading of the bit and word lines
- The solution is to split the memory into "small" memory blocks
- That allows to:
 - use small local word and bit lines \Rightarrow faster access time
 - power down sense amplifiers and disable decoders of non-active memory blocks ⇒ power saving

- Because the contents is permanently fixed the cell design is simplified
- Upon activation of the word line a 0 or 1 is presented to the bit line:
 - If the NMOS is absent the word line has no influence on the bit line:
 - The word line is pulled-up by the resistor
 - A 1 is stored in the "cell
 - If the NMOS is present the word line activates the NMOS:
 - The word line is pulled-down by the NMOS
 - A 0 is stored in the cell
- The NMOS isolates the bit from the word line







- A ground contact has to be provided for every cell
 - a ground rail has to be routed through the cell
 - the area penalty can be shared between two neighbor cells:
 - the odd rows are mirrored around the horizontal axis

- Use close to minimum size pulldown devices to:
 - make the cell size small
 - reduce the bit line capacitance
- R(pull-up) > R(pull-down) to:
 - ensure adequate low level
- Since for large memories the bit line capacitance can be of the order of pF's, low to high transitions will be slow
- A wider pull-up device can be used resulting in a higher V_{OL}
 - this reduces the noise margin but speeds the low-to-high transition
 - to interface with external logic, a sense amplifier is required to restore the logic levels
 - an inverter with adjusted switching threshold can be used as a sense amplifier



- $0 \Rightarrow$ metal-to-diffusion contact
- $1 \Rightarrow \underline{no}$ metal-to-diffusion contact
- only the contact mask layer is used to program the memory array

- Disadvantages:
 - V_{OL} depends on the ratio of the pull-up/pull-down devices
 - A static current path exists when the output is low causing high power dissipation in large memories
- Solution:
 - Use pre-charged logic
 - Eliminates the static dissipation
 - Pull-up devices can be made wider
 - This is the most commonly used structure



- The bit lines are first precharged by the pull-up devices
 - during this phase the word lines must be disabled
- Then, the word lines are activated (word evaluation)
 - during this phase the pull-up devices are off

CMOS regular structures

- The same architecture as a ROM memory
- The pull-down device is modified to allow control of the threshold voltage
- The modified threshold is retained "indefinitely":
 - The memory is nonvolatile
- To reprogram the memory the programmed values must be erased first
- The "hart" of NVRW memories is the Floating Gate Transistor (FAMOS)

- A <u>floating</u> gate is inserted between the gate and the channel
- The device acts as a normal transistor
- However, its threshold voltage is programmable
- Since the t_{ox} is doubled, the transconductance is reduced to half and the threshold voltage increased



- Programming the FAMOS:
 - A high voltage is applied between the source and the gate-drain
 - A high field is created that causes avalanche injection to occur
 - Electrons traverse the first oxide and get trapped on the floating gate ($t_{ox} = 100$ nm)
 - Trapped electrons effectively drop the floating gate voltage
 - The process is self limiting: the building up of gate charge eventually stops avalanche injection
 - The FAMOS with a charged gate is equivalent to a higher V_T device
 - Normal circuit voltages can not turn a programmed device on



- The non-programmed device can be turned on by the word line thus, it stores a "0"
- The word line high voltage can not turn on the programmed device thus, it stores a "1"
- Since the floating gate is surrounded by SiO₂, the charge can be stored for many years



- Erasing the memory contents (EPROM):
 - Strong UV light is used to erase the memory:
 - UV light renders the oxide slightly conductive by direct generation of electron-hole pairs in the SiO₂
 - The crasure process is slow (several minutes)
 - Programming takes 5-10 μ s/word
 - Number of erase/program cycles limited (<1000)
- Electrically-Erasable PRCM (E²PROM)
 - A reversible tunneling mechanism allows
 E²PROM's to be both electrically programmed and erased

- Static Read-Write Memories (SRAM):
 - data is stored by positive feedback
 - the memory is volatile
- The cell use six transistors
- Read/write access is enabled by the word-line
- Two bit lines are used to improve the noise margin during the read/write operation
- During read the bit-lines are pre-charged to V_{dd}/2:
 - to speedup the read operation
 - to avoid erroneous toggling of the cell



- SRAM performance:
 - The read operation is the critical one:
 - It involves discharging or charging the large bit-line capacitance through the small transistors of the cell
 - The write time is dominated by the propagation delay of the cross-coupled inverter pair
 - The six-transistor cell is not area efficient:
 - It requires routing of two power lines, two bit lines and a word line
 - Most of the area is taken by wiring and interlayer contacts



- Resistive-load SRAM
 - employs resistors instead of PMOS's
 - The role of the resistors is only to maintain the state of the cell:
 - they compensate for leakage currents (10^{-15A})
 - they must be made as high as possible to minimize static power dissipation
 - undoped polysilicon $10^{12}\Omega/$
 - The bit-lines are pre-charged to V_{dd}:
 - the low-to-high transition occurs during precharge
 - the loads contribute "no" current during the transitions
 - The transistor sizes must be correctly chosen to avoid toggling the cell during read



- Dynamic Random-Access Memory (DRAM)
 - In a dynamic memory the data is stored as charge in a capacitor
- Tree-Transistor Cell (3T DRAM):
 - Write operation:
 - Set the data value in bit-line 1
 - Assert the write word-line
 - Once the WWL is lowered the data is stored as charge in C
 - Read operation:
 - The bit-line BL2 is pre-charged to Vdd
 - Assert the read word-line
 - if a 1 is stored in C, M2 and M3 pull the bit-line 2 low
 - if a 0 is stored C, the bit-line 2 is left unchanged



Trieste, 9-13 November 1998 CMOS regular structures

- The cell is inverting
- Due to leakage currents the cell needs to be periodically refreshed (every 1 to 4ms)
- Refresh operation:
 - · read the stored data
 - put its complement in BL1
 - enable/disable the WWL
- Compared with an SRAM the area is greatly reduce:
 - SRAM \Rightarrow 1092 λ^2
 - DRAM \Rightarrow 576 λ^2
 - The are reduction is mainly due to the reduction of the number of devices and interlayer contacts



(from J. M. Rabaey 1996)

- One-Transistor dynamic cell (1T DRAM)
 - It uses a single transistor and a capacitor
 - It is the most widely used topology in commercial DRAM's
- Write operation:
 - Data is placed on the bit-line
 - The word-line is asserted
 - Depending on the data value the capacitance is charged or discharged



Trieste, 9-13 November 1998 CMOS regular structures

- Read operation:
 - The bit-line is pre-charged to V_{dd}/2
 - The word-line is activated and charge redistribution takes place between C_s and the bit-line
 - This gives origin to a voltage change in the bitline, the sign of which determines the data stored:

$$\Delta V = \left(V_{BIT} - \frac{V_{dd}}{2}\right) \frac{C_S}{C_S + C_{BL}}$$

- C_{BL} is 10 to 100 times bigger than $C_S \Rightarrow$ ∆V≅250mV



- The amount of charge stored in the cell is modified during the read operation
- However, during read, the output of the sense amplifier is imposed on the bit line restoring the stored charge

- Contrary to the previous cases a 1T cell <u>requires</u> a sense amplifier for correct operation
- Also, a relatively large storage capacitance is necessary for reliable operation
- A 1 is stored as V_{dd}-V_T. This^{Storage Node Poly} reduces the available charge: 2nd Field Oxid
 - To avoid this problem the word-line can be bootstrapped to a value higher than Vdd



- Sense amplifiers improve the speed performance of the memory cell:
 - they compensate for the low driving capability of the cells
- Contribute to power reduction by allowing to use low signal swings on the heavily capacitive bit-lines
- They perform signal restoration in the refresh and read cycles of 1T dynamic memories
- They can be differential or single ended



SRAM read cycle:

- pre-charge:
 - pre-charge the bit-lines to
 V_{dd} and make their voltages
 equal
- Reading:
 - disable the pre-charge devices
 - enable the word lines
 - once a minimum (≅0.5V) signal is built up in the bitlines the sense amplifier is turned on
- The grounded PMOS loads limit the signal swing and facilitate the next pre-charge



A cross-coupled inverter pair can be used as a sense amplifier

- To act as a sense amplifier:
 - The bit-lines are equalized: this initializes the flip-flop in its metastable point
 - A voltage is built over the bit lines by the selected cell
 - The sense amplifier is activated once the voltage is large enough
 - The cross-coupled pair then toggles to one of its stable operating points
 - The transition is fast due to positive feedback
- Ideal for an 1T DRAM: inputs and outputs are merged



- The memory array is divided in two: the sense amplifier in the middle
- On each side "dummy" cells are added
- These cells serve as a reference during the reading

- EQ is asserted and both halves pre-charged to V_{dd}/2
- The dummy cells are also precharged to $V_{dd}/2$
- If a cell in one of the halves of the bit line is selected, the dummy cell on the other half is used as a reference for the sense amplifier



Trieste, 9-13 November 1998 CMOS regular structures